411

| Notice of Allowability | Application No. | Applicant(s) | |
|---|---|---|--------------------|
| | 10/709,699 | CHENG ET AL. | |
| | Examiner | Art Unit | |
| | Thao P. Le | 2818 | |
| The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313 | (OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to | olication. If not include will be mailed in due of | d course. THIS |
| 1. This communication is responsive to 3/14/05. | | | |
| 2. ☑ The allowed claim(s) is/are <u>17-36</u> . | | | |
| 3. \boxtimes The drawings filed on <u>24 May 2004</u> are accepted by the Ex | kaminer. | | |
| 4. ☐ Acknowledgment is made of a claim for foreign priority ur a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have 3. ☐ Copies of the priority documents have 3. ☐ Copies of the priority documents have 4. ☐ CERTIFIED COPIES NOT EXTENDED IT. 4. ☐ ADDITION (POPTIES NOT EXTENDED IT. 5. ☐ A SUBSTITUTE OATH OR DECLARATION must be submoved in the priority of the priority which give the priority of | e been received. been received in Application No cuments have been received in this r | complying with the requestion of the front (not the d). | uirements OTICE OF |
| Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date 5/24/04 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material | 5. Notice of Informal P 6. Interview Summary Paper No./Mail Dat 7. Examiner's Amendn 8. Examiner's Stateme 9. Other | (PTO-413), e nent/Comment | |

Art Unit: 2818

DETAILED ACTION

Election/Restriction

1. Examiner confirms that Applicants elected to prosecute group I (previously presented claims 17-20 and newly added claims 21-36) and have canceled group II (claims 1-16) without prejudice.

2. The Amendment filed on 03/14/05 has been entered.

The specification has been amended.

Claims 1-16 have been canceled.

Claim 17 has been amended.

Claims 21-36 have been newly added.

Information Disclosure Statement

3. Information Disclosure Statement (IDS) filed on **05/24/04** and made of record.

The references cited on the PTOL 1449 form have been considered.

EXAMINER'S AMENDMENT

4. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Art Unit: 2818

5. Authorization for this examiner's amendment was given in a telephone interview with Attorney Graham S. Jones, II (Tel. 845-473-9118) on 03/23/05. The Application has been amended as follows:

- a) Amend the specification, paragraph 0146, line 5, replace "same as in FIGS. 4A-4GE" by
 - --- same as in FIGS. 4A-4G ----
 - b) Replace claim 17 as following:
 - 17. A semiconductor device on a semiconductor substrate, comprising:

an array of parallel trenches formed on the semiconductor substrate comprising alternating wide trenches and narrow trenches;

a <u>plurality of</u> first electrodes formed in the narrow trenches composed of a first fill material of a first conductivity type;

a <u>plurality of</u> second electrodes formed in the wide trenches composed of a second fill material of an opposite conductivity type;

a first <u>set of outdiffusion regions</u> doped with dopant diffused from the first electrode into a region in the substrate about the periphery of the <u>corresponding</u> narrow trench; and

a second <u>set of outdiffusion regions</u> doped with dopant diffused from the second electrode into a region in the substrate about the periphery of the <u>corresponding</u> wide trench.

Art Unit: 2818

c) Amend claim 30 as following:

Add "29" after "claim", before "including", ---- the photodetector device of claim 29 including----

d) Amend claim 35 as following:

In line 10, replace "diffused from a first electrode" by --- diffused from the first electrode ---

In line 12, replace "diffused from a second electrode" by --- diffused from the second electrode ---

Reasons for Indication of Allowable Subject Matter

6. Claims 17-36 are allowed.

The following is a statement of reason for the indication of allowable subject matter:

a) A set of claims 17-28 and 35-36:

Claims 17-28 and 35-36 are considered allowable since none of the prior art made of record and considered pertinent to the applicant's disclosure teach or suggest the claimed limitations having a semiconductor device on a semiconductor substrate comprising an array of parallel trenches formed in the substrate comprising alternating wide trenches and narrow trenches and among other features cited in independent claims 17 and 35.

b) A set of claims 29-34:

Claims 29-34 are considered allowable since none of the prior art made of record and considered pertinent to the applicant's disclosure teach or suggest the claimed limitations having a photodetector device formed on a semiconductor substrate comprising a wide trench and a narrow trench formed in the substrate, a first electrode formed in the narrow trench of a deposit of a first fill material filling the wide trench partially and filling the narrow trench completely, an epitaxial semiconductor layer formed in the wide trench leaving a narrowed wide trench therein and then a second electrode formed in the wide trench by a second fill material and among other features cited in independent claim 29.

7. If Applicants are aware of better art than that which has been cited, they are required to call such to attention of the examiner.

Conclusion

- 8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- 9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao P. Le whose telephone number is 571-272-1785. The examiner can normally be reached on M-T (7-6).

Art Unit: 2818

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on 571-272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao P. Le Examiner Art Unit 2818

March 24, 2005.